

Please rewrite the Abstract as follows:

The plasma flux distribution on a workpiece of an inductive plasma processor is controlled. The processor includes a plasma excitation coil having a center axis and plural parallel connected windings adapted to be driven by an excitation source. The parallel windings are concentric with the axis so an exterior winding of the coil surrounds the remainder of the coil. The exterior winding is turned about the axis relative to another winding of the coil so the plasma density incident on the workpiece has a predetermined desired relationship.